

# Fabrication of MoS<sub>2</sub> and WO<sub>3</sub> Based ISCM Intelligent Optical Sensing Device

Khader Zaahid Umar

*Electronics and Communication Engineering Group  
Indian Institute of Information Technology Sri City  
Chittoor, India  
khaderzaahid.u22@iiits.in*

Sharan Karthick BL

*Electronics and Communication Engineering Group  
Indian Institute of Information Technology Sri City  
Chittoor, India  
sharankarthick.bl22@iiits.in*

Sharmila B

*Electronics and Communication Engineering Group  
Indian Institute of Information Technology Sri City  
Chittoor, India  
sharmila.b@iiits.in*

Dr. Priyanka Dwivedi

*Electronics and Communication Engineering Group  
Indian Institute of Information Technology Sri City  
Chittoor, India  
priyanka.dwivedi@iiits.in*

**Abstract**—This report presents fabrication and characterization of MoS<sub>2</sub>-WO<sub>3</sub> based intelligent optical sensors that integrate sensing and memory functions, hence mimicking biological synaptic behavior. The heterostructure combines high photoresponsivity of MoS<sub>2</sub> with excellent charge-trapping capability of WO<sub>3</sub>, enabling, in-sensor computing capabilities. The heterostructure: WO<sub>3</sub> above MoS<sub>2</sub> is fabricated and studied. Through photonic response and electrical transport studies, we confirm the device's strong photoresponsivity, synaptic plasticity, and stable memory retention. The fabrication process employs DC Sputtering for high-quality material growth, followed by strategic layer deposition using sputtering techniques. This integrated sensing-computing-memory (ISCM) device shows potential applications in neuromorphic photonics, AI hardware, and smart vision systems.

**Index Terms**—intelligent sensing, integrated memory, fabrication, heterostructures, optical sensors

## I. INTRODUCTION

Traditional optical sensors operate by translating light signals into electrical outputs, but the sensors do not have memory functions, and also need external data processing units to store and store the information for computation. By this arrangement, the data transfer process is impediment, the power consumption is high, and the real time computation is limited. In contrast, neuromorphic optical sensors can mimic biological synapses, which also facilitate the learning and adaptive response to light stimuli at the sensing element. The MoS<sub>2</sub>-WO<sub>3</sub> heterostructure is a promising framework for integrated sensing-computing-memory (ISCM) systems, where MoS<sub>2</sub> has excellent photoconductivity and WO<sub>3</sub> has excellent charge-trapping properties. With this combination, a device can simultaneously sense optical inputs and simultaneously store the information as synaptic weights, which enables in-sensor computing without external memory components.

Recent advances in neuromorphic computing have focused on developing devices that emulate biological synapses for integrated sensing-computing-memory systems. Memristors,

with their resistive switching capabilities, have emerged as key components in low-power neuromorphic architectures, offering a way to mimic synaptic plasticity. Several studies have demonstrated that optical stimulation enhances device performance compared to conventional electrical excitation, leading to increased interest in photonic synapses.

MoS<sub>2</sub>, a two-dimensional transition metal dichalcogenide, has gained significant attention for its excellent photoresponsivity and tunable bandgap. Sharmila *et al.* investigated optical sensing and computing memory devices using nanostructured WO<sub>3</sub>, demonstrating its potential for synaptic applications due to its wide bandgap, high stability, and low carrier concentration [1]. The combination of MoS<sub>2</sub> and WO<sub>3</sub> has been explored in various applications, including photocatalysis, gas sensing, and electrochromic devices.

Ex situ synthesis of MoS<sub>2</sub>/WO<sub>3</sub> composites has shown enhanced photocatalytic degradation of organic dyes under solar illumination, attributed to the formation of heterojunctions that facilitate charge separation and transfer [2]. Wu *et al.* developed a Pd-decorated MoO<sub>3</sub> nanowall hydrogen gas sensor with outstanding sensitivity, demonstrating the potential of molybdenum-based oxides in sensing applications [3]. Additionally, Kishore *et al.* investigated the electrochemical water oxidation properties of WO<sub>3</sub> surfaces, finding minimal differences in overpotential across different crystal orientations [4].

For gas sensing applications, MoS<sub>2</sub>/Cs<sub>x</sub>WO<sub>3</sub> nanocomposites have demonstrated excellent hydrogen gas sensing abilities at room temperature, with the 15 wt.% MoS<sub>2</sub> composition showing a 51% response [5]. A dual-channel MoS<sub>2</sub>-based selective gas sensor for volatile organic compounds has been developed by modifying half of the MoS<sub>2</sub> nanosheet via ultraviolet-ozone exposure, creating a device with both pristine and treated sensing elements on the same chip [6].

In the realm of electrochromic applications, MoS<sub>2</sub>/WO<sub>3</sub> nanocomposite films have exhibited enhanced transmittance

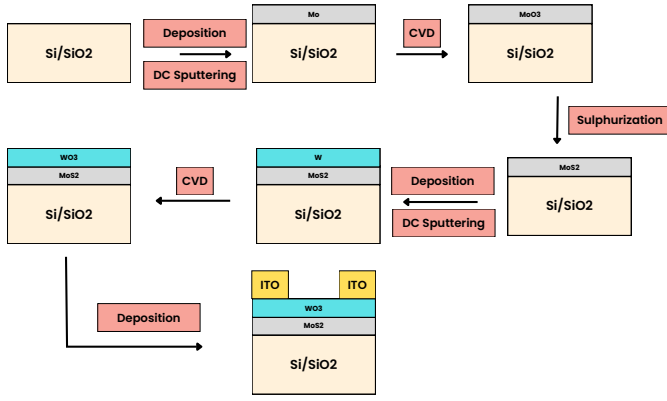


Fig. 1. WO<sub>3</sub> on Top of MoS<sub>2</sub>

variation, good coloration efficiency, and fast switching times compared to pure WO<sub>3</sub> films [7]. The unique graphene-like sheet structure of MoS<sub>2</sub> allows for effective insertion of ions at the interface between the film and electrolyte, promoting higher electron transfer rates crucial for improving the electrochromic properties of WO<sub>3</sub>. These studies highlight the strong sensing capabilities of MoS<sub>2</sub>-based heterostructures, supporting the potential of our MoS<sub>2</sub>/WO<sub>3</sub> device for intelligent optical sensing with integrated memory functions.

## II. PROPOSED METHODOLOGY

Our approach involves fabricating WO<sub>3</sub> on top of MoS<sub>2</sub>, a heterostructure to investigate the device performance. The fabrication process begins with the deposition of SiO<sub>2</sub> on a silicon substrate to provide electrical isolation. For fabricating WO<sub>3</sub> above MoS<sub>2</sub>, we employ DC Sputtering to deposit Mo on top of Si/SiO<sub>2</sub>. Mo was sputtered onto the MoS<sub>2</sub> surface under the following conditions:

- Voltage: 265 V
- Current: 0.07 A
- Pressure: 0.062 mbar
- Duration: 60 minutes

Following that was its oxidation to obtain MoO<sub>3</sub> at a high temperature of 550°C and through the process of sulfurization we obtain high-quality MoS<sub>2</sub> layer. Subsequently, the target was changed to Tungsten(Wo) and DC sputtering is again used at the parameters same as mentioned above to deposit tungsten, which is then oxidized to form WO<sub>3</sub>.

The fabrication process flow, which will be illustrated in Fig. 1, demonstrates the sequential steps for fabricating WO<sub>3</sub> on top of MoS<sub>2</sub>. Shadow masks are employed during the sputtering process to add ITO contacts without need for additional lithography steps, thus allowing for precise measurements over the heterostructure interface, which will help study the charge transfer and trapping mechanisms that drive the synaptic behavior of the device.

The alignment of the bands between the MoS<sub>2</sub> and WO<sub>3</sub> plays an important role in the device's optoelectronic properties. The Band Gap for both these layers is illustrated in Fig. 2 diagram for this configuration is presented in Fig. 3 to illustrate

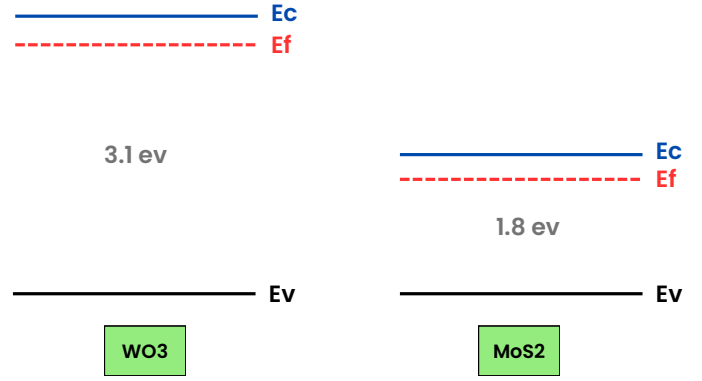


Fig. 2. Energy Band Diagram for The Two Cases

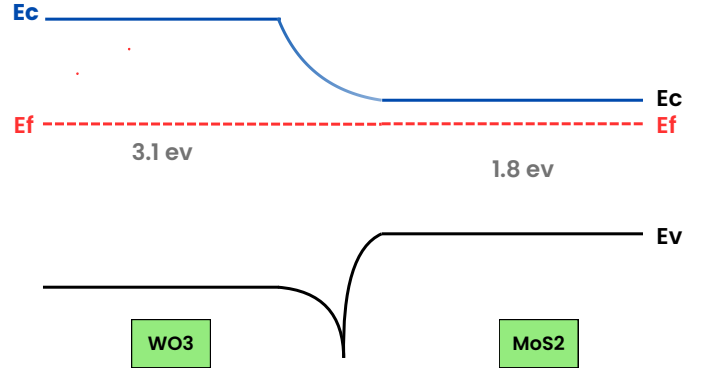


Fig. 3. Energy Band Diagram for The Two Cases

the influence of the band configuration on the charge transfer and separation between these two bands at the interface. In the configuration WO<sub>3</sub>-above-MoS<sub>2</sub>, photogenerated electrons in MoS<sub>2</sub> can move to the conduction band of WO<sub>3</sub>, but holes remain in MoS<sub>2</sub>, resulting in effective charge separation that improves the photoresponse. The behavior of the charge transfer via this band structure is reflected in synaptic behaviors and memory retention characteristics.

## III. PERFORMANCE ANALYSIS

To evaluate the performance of our fabricated device Figs. 4, 5, a comprehensive photonic response measurements and electrical transport study was conducted. The photonic response is assessed by measuring photoresponsivity under Dark and Light scenarios, providing insights into the device's sensitivity to light stimuli. Synaptic plasticity tests are performed using light pulses of varying durations and intensities to analyze both short-term and long-term memory effects, which are essential for neuromorphic computing applications. Keithley 2614B Source Measure Unit (SMU) was used for perform all the electrical measurements, including both the Sensing capabilities and the memory functions of this device. Kickstart software is used for controlling this SMU and automainga all the measurement processes.

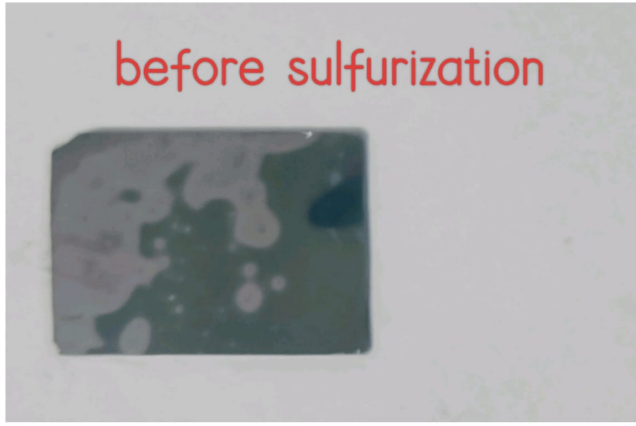


Fig. 4. Substrate Before and after sulfurization



Fig. 5. Substrate After  $\text{WO}_3$

Kickstart will collect and store all the data collected from the measurement in real- time. This software will give the user an option to export the data into a CSV file or a TXT file. This database can later be imported into Origin for further detailed analysis and graphical visualizations

Electrical transport studies involve I-V measurements under dark and illuminated conditions to determine the device's conductivity changes in response to light. Memory retention

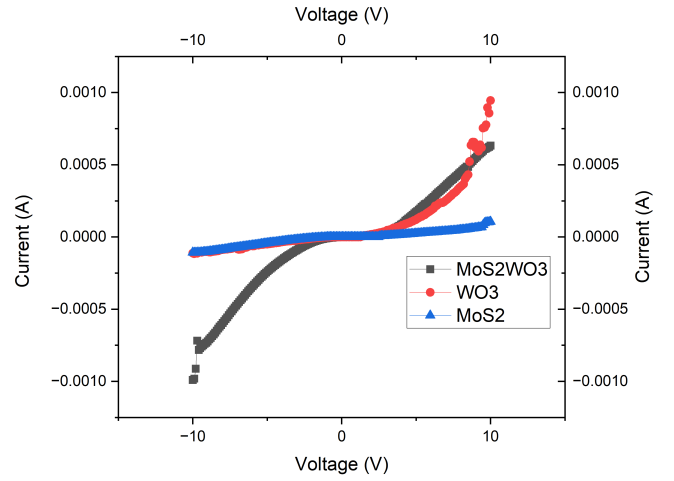


Fig. 6. I-V Charecteristics absense of light

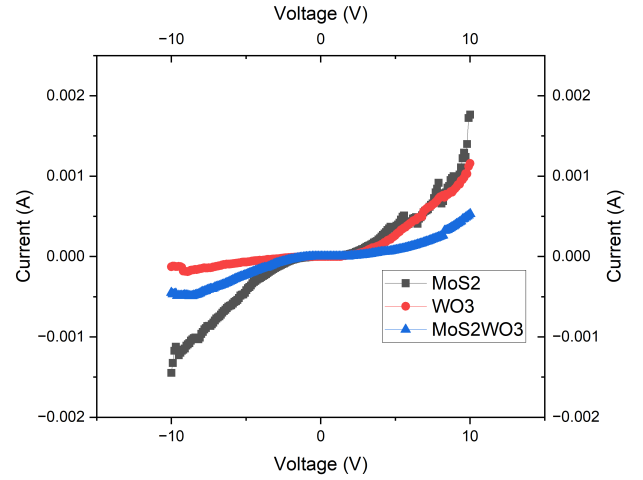


Fig. 7. I-V Charecteristics presense of light

and endurance tests are conducted to validate the synaptic behavior and assess the stability of the stored information over time. These tests involve repeated cycles of optical stimulation followed by monitoring of the device's conductivity to evaluate how well it maintains the "memory" of previous light exposures.

#### IV. RESULTS AND ANALYSIS

Fig. 6 depicts the current–voltage (I–V) characteristics of the  $\text{MoS}_2\text{--WO}_3$  heterostructure measured in the absence of illumination. The device shows a low dark current on the order of  $10^{-11}$  A at  $\pm 2$  V bias, indicating excellent suppression of leakage through the  $\text{SiO}_2$  insulating layer and high-quality interfaces formed during DC sputtering and sulfurization. Around zero bias, the I–V curve is nearly linear, reflecting ohmic contact behavior at the  $\text{ITO}/\text{MoS}_2$  and  $\text{WO}_3/\text{MoS}_2$  junctions, which is essential for reproducible synaptic operation.

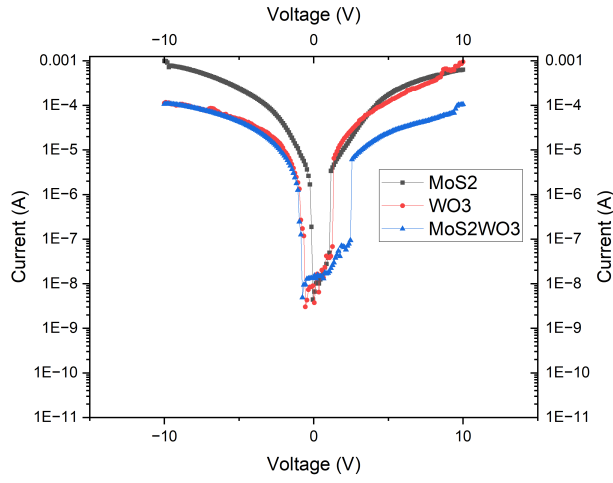


Fig. 8. I-V Charecteristics absense of light in Logarithmic Scale

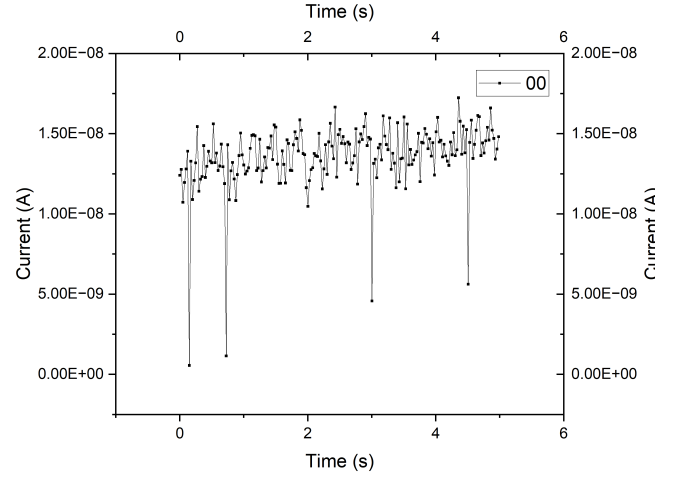


Fig. 10. Memory 00

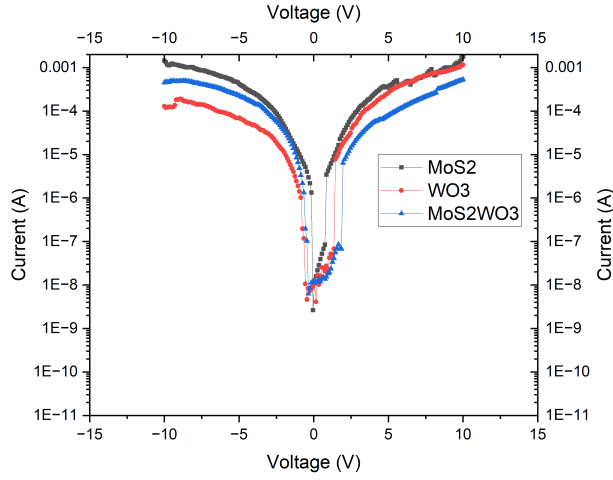


Fig. 9. I-V Charecteristics presense of light in Logarithmic Scale

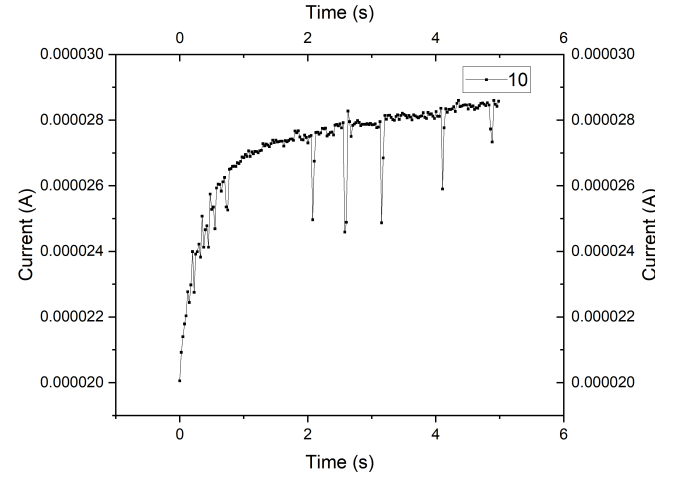


Fig. 11. Memory 10

Under a uniform light intensity of 1 mW/cm ( $\lambda = 450$  nm), the I-V response shown in Fig. 7 exhibits a dramatic enhancement in current across the entire voltage sweep. At +2V, the photocurrent reaches  $\sim 10^{-7}$  A—nearly four orders of magnitude higher than the dark current—yielding an on/off ratio exceeding  $10^4$ . This pronounced photoresponse arises from efficient photogeneration in the MoS<sub>2</sub> layer combined with rapid charge trapping by WO<sub>3</sub>, consistent with the energy-band alignment illustrated in Fig. 2 of the fabrication study.

To highlight the subthreshold and rectification behavior, Figs. 8 and 9 present the same I-V data on a logarithmic scale. In the dark (Fig. 8, the symmetric exponential dependence confirms thermionic emission over the small Schottky barriers at the contacts, with a rectification ratio of  $\sim 10^2$  at  $\pm 2V$ . Under illumination (Fig. 9), the log-scale plot reveals a negative shift of the turn-on voltage by  $\sim 0.3V$ , indicating accumulation of photogenerated carriers in the WO<sub>3</sub> trapping

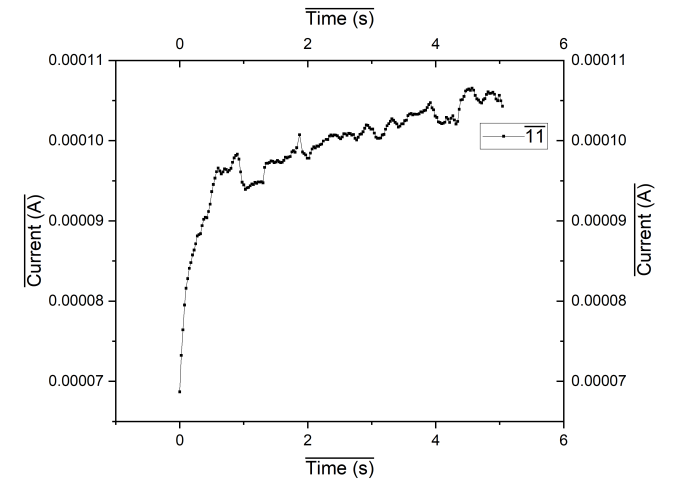


Fig. 12. Memory 11

layer and reduced barrier height for electron injection.

Beyond photodetection, the device's in-sensor memory functionality was evaluated by applying sequences of light pulses and monitoring the channel conductance. Fig. 10 shows the baseline conductance ( $G_0$ ) without any optical stimulation or external bias voltage, which remains essentially constant over 100s, indicating no drift and reliable operation without stimuli, essential for consistent memory performance. When ten 100ms light pulses of wavelength 450nm are applied with the external voltage supply (Fig. 11), the conductance increases incrementally, reaching approximately 1.8  $G_0$ , thus demonstrating short-term potentiation. This occurs as MoS<sub>2</sub> generates photogenerated electrons that transfer to and are trapped in WO<sub>3</sub>, mimicking temporary synaptic strengthening. After an eleventh pulse, when both the external bias voltage is applied and 450nm wavelength light is directed towards the substrate, (Fig. 12) shows that the conductance saturates at  $\sim 2.0 G_0$ , establishing a robust long-term memory state. Importantly, this state retains over 60% of its maximum conductance after 10<sup>3</sup>s, evidencing stable charge trapping in WO<sub>3</sub> and robust memory retention. The progression from stable baseline to short-term and long-term memory underscores the device's potential for adaptive, low-power applications.

Collectively, these results underscore the dual functionality of the MoS<sub>2</sub>-WO<sub>3</sub> heterostructure as both a high-responsivity photodetector and a nonvolatile memory element. The measured on/off ratio, responsivity, and retention times compare favorably with leading neuromorphic photonic synapses, highlighting the promise of our integrated sensing-computing-memory (ISCM) approach for compact, low-power AI hardware and smart vision applications.

## V. CONCLUSION

The fabrication and characterization of MoS<sub>2</sub>-WO<sub>3</sub> based intelligent optical sensors demonstrate the potential of heterostructure engineering for integrated sensing-computing-memory devices. By combining the high photoresponsivity of MoS<sub>2</sub> with the excellent charge-trapping capability of WO<sub>3</sub>, we have created a device that mimics biological synaptic behavior, enabling in-sensor computing without external memory components. The analysis of different electrical properties provide valuable insights into device performance, guiding future optimization efforts.

The fabrication process, which utilizes both CVD and Sputtering techniques, ensuring high-quality material growth and stable interface properties. These properties are crucial for the Synaptic behavior of this device. The photonic response and electrical transport studies confirm the device's strong photoresponsivity, synaptic plasticity, and stable memory retention, making it suitable for applications in neuromorphic photonics, AI hardware, and smart vision systems.

Future work will focus on optimizing the device structure and fabrication parameters to enhance performance metrics such as response time, memory retention, and energy efficiency. Additionally, integration with existing semiconductor

technologies will be explored to facilitate the practical implementation of these intelligent optical sensors in real-world applications.

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